press release
13 August 2009

Annealsys presents its new catalog of CVD, MOCVD and Spray CVD systems

MC100
4-inch MOCVD reactor

MC050
2-inch MOCVD reactor
In-situ annealing

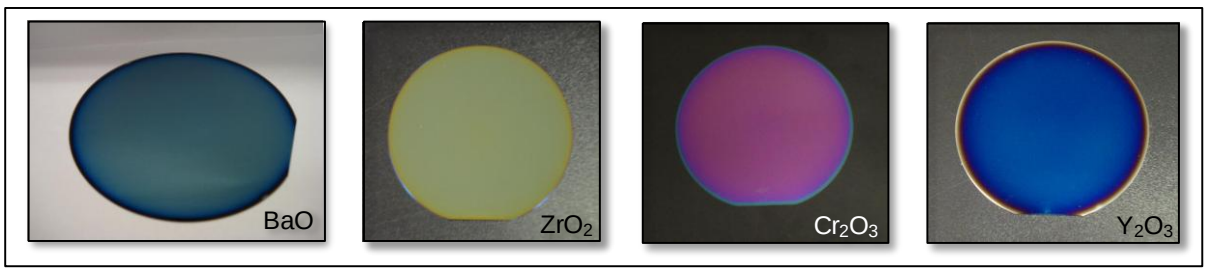
SprayCVD-050
2-inch SprayCVD reactor
In-situ annealing

These reactors were specially developed for R&D applications. They allow doing heteroepitaxy of oxides, metals and transition metal nitrides and other materials on a wide range of substrates by MOCVD and Spray CVD using solid and liquid organometallic volatile precursors. They can support different types of vaporizers, up to 4 precursor lines and a vacuum system adapted to your application. The reactors are easy to clean for fast switching to another application.

Precursors are delivered by optimized liquid panels and tanks specially designed to use air-sensitive precursors and to reduce precursors losses during the rinsing steps.

The lamp heating system in MC-050 and SprayCVD-050 allows in-situ annealing.

Examples of deposition realized on Annealsys reactors and direct liquid injection (DLI) evaporators developed by Kemstream (www.kemstream.com). This technology allows using a wide range of chemicals including low vapor pressure precursors, solid precursors dissolved into liquids and thermally unstable precursors. These tools allow deposition of a wide range of new materials.



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